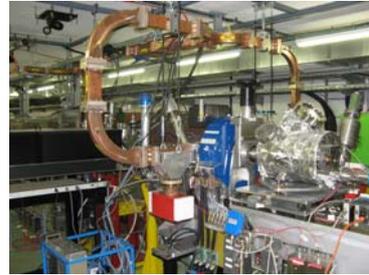




Electron and Ion Sources Layout

- ◆ **Electron Sources**
 - Thermionic
 - Photo-Cathodes

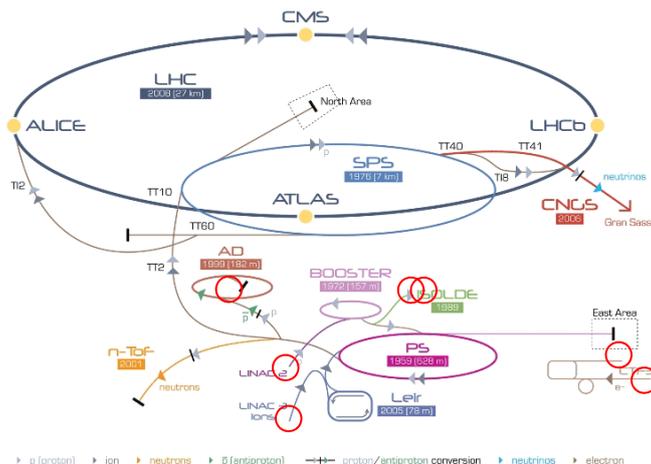
- ◆ **Ion Sources**
 - Particle motion in plasmas
 - Protons
 - ECR Ion Source
 - Negative Ions



Richard Scrivens, BE Dept, CERN.
CAS@CERN, November 2013



Electron and Ion Sources Every accelerator chain needs a source!



LHC Large Hadron Collider SPS Super Proton Synchrotron PS Proton Synchrotron
 AD Antiproton Decelerator CTF-3 Clio Test Facility CNCS CERN Neutrinos to Gran Sasso ISOLDE Isotope Separator On-Line DEvis
 LEIR Low Energy Ion Ring LINAC LINear ACcelerator n-TbF Neutrons Time Of Flight

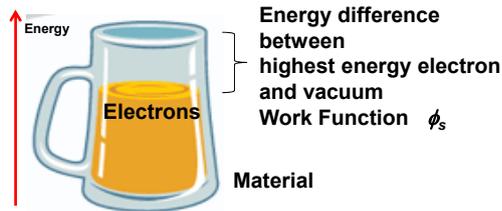


Electron and Ion Sources

Electrons – Thermionic Emission

Electrons within a material are heated to energies above that needed to escape the material.

Cathode emission is dominated by the Richardson Dushman equation.



3



Electron and Ion Sources

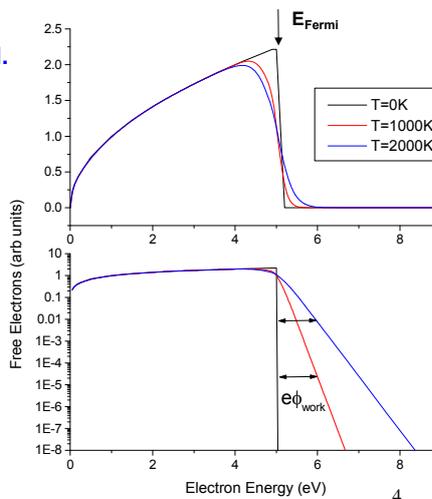
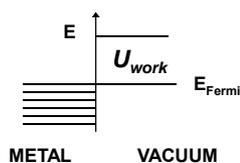
Electrons – Thermionic Emission (the maths)

Conducting materials contain free electrons, who follow the Fermi-Dirac energy distribution inside the material.

When a material is heated, the electrons energy distribution shifts from the zero temperature Fermi distribution.

$$n(E)dE = \left[\frac{4\pi(2m_e)^{3/2}}{h^3} \right] \left[\frac{\sqrt{E}}{1 + \exp\left(\frac{E - E_{Fermi}}{kT}\right)} \right] dE$$

Electrons above the work function energy, can be removed from the material.





Electron and Ion Sources

Electrons – Thermionic Emission (the maths)

- ◆ Therefore at high temperatures there is an **ELECTRON CLOUD** around the material. The current density can then be found by integrating the available electrons and their energy.

$$J = nve$$

$$J = A \cdot T^2 \exp\left(\frac{-eU_{work}}{kT}\right)$$

$$A = \frac{4\pi m_e k^2}{h^3} \approx 1.2 \times 10^6 \text{ Am}^{-2} \text{ K}^{-2}$$

This electron current is available to be pulled off the surface...
Richardson-Dushman equation
Rev. Mod. Phys. 2, p382 (1930)

This factor **A** is not achieved in practice.

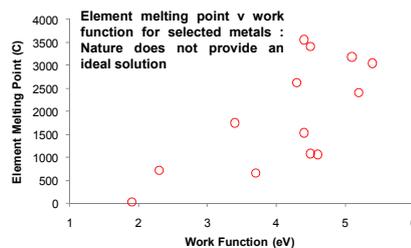
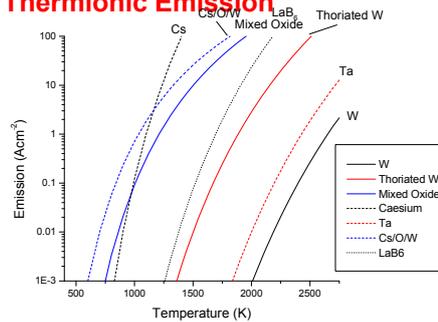


Electron and Ion Sources

Electrons – Thermionic Emission

	A $\text{Acm}^{-2}\text{K}^{-2}$	U_{work} eV
W	60	4.54
W Thoriated	3	2.63
Mixed Oxide	0.01	1
Cesium	162	1.81
Ta	60	4.12
Cs/O/W	0.003*	0.72*
LaB ₆	29	2.66

*- A and work function depend on the Cs/O layer Thickness and purity

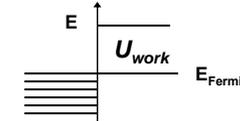




Electron and Ion Sources

Electrons – Photo Emission

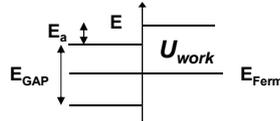
- ◆ The energy of an electron in a material can be increased above the vacuum energy by absorbing photons - photoelectric effect.



METAL VACUUM

$$\lambda_c = \frac{hc}{eU_{work}} = \frac{1239.8}{U_{work}}$$

	U_{work} (eV)	λ_c (nm)
W	4.5	275
Mg	3.67	340
Cu	4.65	267



SEMI-COND VACUUM

$$\lambda_c = \frac{hc}{E_{GAP} + E_a} = \frac{1239.8}{E_{GAP} + E_a}$$

	$E_g + E_a$ (eV)	λ_c (nm)
GaAs	5.5	225
Cs:GaAs	*	*
Cs ₂ Te	~3.5	350
K ₂ CsSb	2.1	590

Cs:GaAs – Surface Caesiated GaAs
can be used with 532nm radiation. Requires
Recaesiation after a few hundred C extraction.



Electron and Ion Sources

Electrons – Photo Cathodes

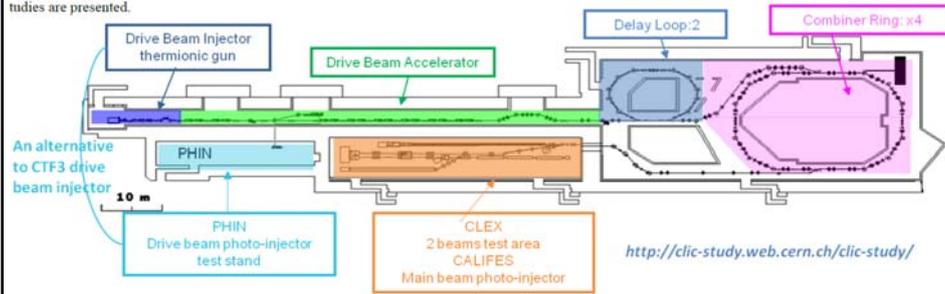
- ◆ **Quantum Efficiency = Electrons/photon [$Q_e(\lambda)$]**
 - GaAs:Cs=17% , CsTe=12.4% , K2CsSb=29%, Cu~0.01%,
- ◆ **METALS**
 - Poor quantum efficiency leads to low intensity electron beams.
 - At high optical powers, a plasma is formed.
 - Very robust material.
- ◆ **SEMICONDUCTORS**
 - Can find materials optical wavelengths with high quantum efficiency (cf Photo Cathode Tubes).
 - Difficult to use in a high radiation area of an electron-gun (x-rays and ions cause decomposition and surface damage).
 - GaAs:Cs has high QE at 532nm – High power lasers available. Cs surface not suited to RF guns.
 - Cs₂Te (Cesium Telluride)– High Quantum efficiency but needs UV lasers.



Electron and Ion Sources

CTF3 – Electron Guns

studies are presented.



CTF3 has three electron guns.

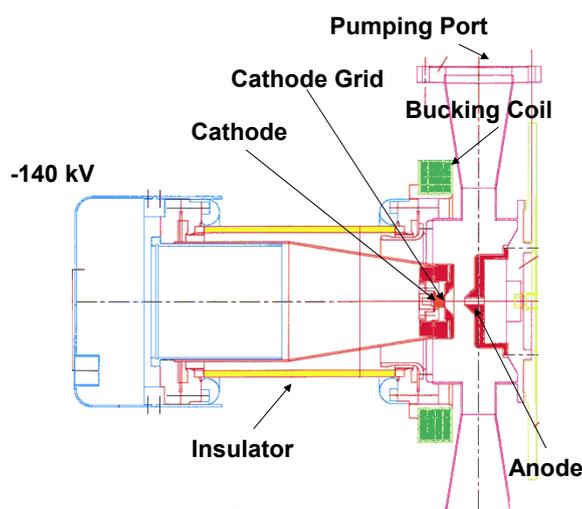
1. A thermionic Gun for the drive beam generation
2. A test photo-emission and RF gun as a test facility for the drive beam.
3. A photo-emission and RF gun for the probe beam.

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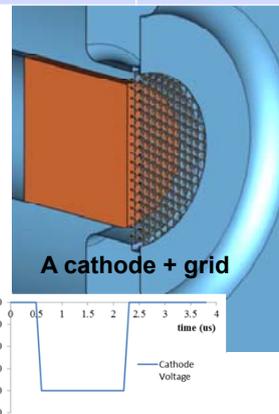
Electron and Ion Sources

CTF3 Thermionic Gun



Disclaimer: These are not actual CTF3 systems

Electron Current	5 A
Electron Energy	140 keV
Emittance	15-20 mm.mrad
Pulse	1.4us @ 5 Hz





Electron and Ion Sources

CTF3 Thermionic Gun

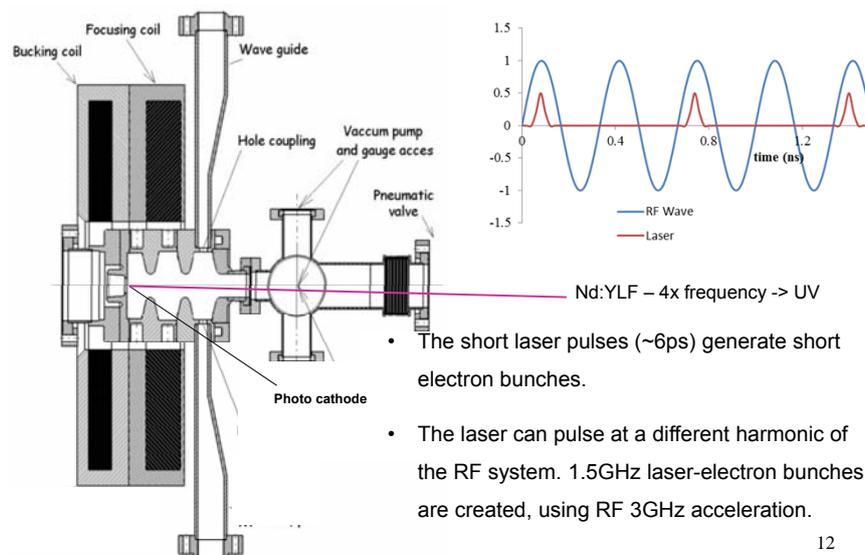
The accelerator layout after the gun

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Electron and Ion Sources

CTF3 – CALIFES – probe beam photo gun



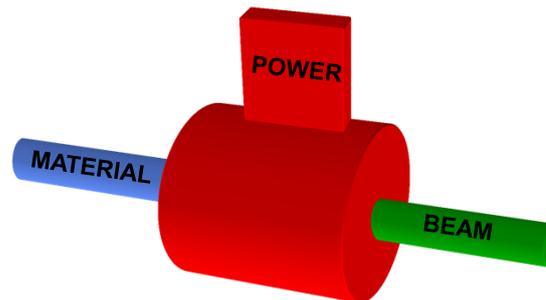
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Electron and Ion Sources

Ion Sources - Basics

- ◆ An Ion Source requires an “ion production” region and an “ion extraction” system.
- ◆ In most (but not all) cases, ion production occurs in a plasma.



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Electron and Ion Sources

Ion Sources - Basics

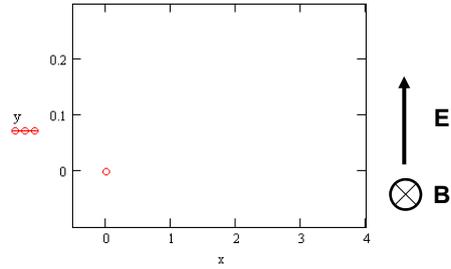
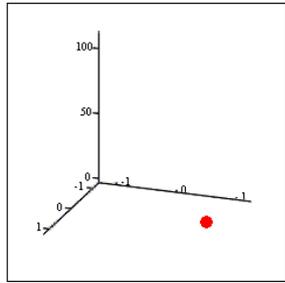
- ◆ Plasma Processes
 - Electron heating
 - Plasma confinement (electric and magnetic)
 - Collisions (e-e, e-i, i-e, i-i + residual gas)
 - Atomic processes (ionisation, excitation, disassociation, recombination)
 - Surface physics (coatings + desorption, e-emission)
 - Mechanical processes (chamber heating+cooling, erosion)
- ◆ Ion Source Goal -> Optimise these processes to produce the required ion type and pulse parameters.
- ◆ AND maximize reliability, minimize emittance, power and material consumption.

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Electron and Ion Sources

Plasma Particle Motion



$$\rho_L = \frac{\sqrt{2mE_\perp}}{eB}, \omega_L = \frac{eB}{m}$$

$$v_{drift} = \frac{\vec{E} \times \vec{B}}{B^2}$$

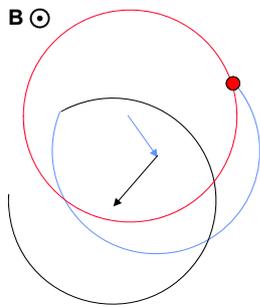
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Electron and Ion Sources

Plasma Particle Motion

$$D \sim \rho_L^2 v_c \sim \left(\frac{\sqrt{2m_p E_\perp}}{eB} \right)^2 \frac{1}{T^{3/2}} \left(\frac{m_e}{m_p} \right)^{1/2} \sim \frac{m_p^{1/2}}{T^{1/2}}$$



cf: opposite to classical energy - velocity equation !

$$v = \left(\frac{2E}{m} \right)^{1/2}$$

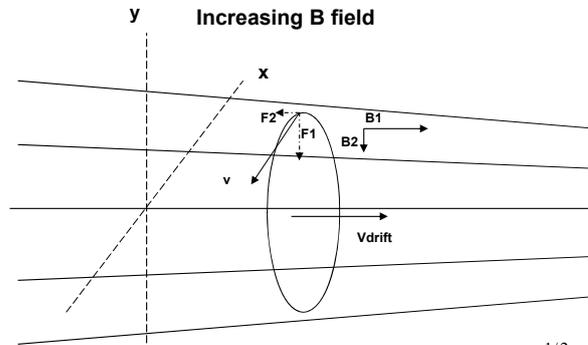
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Electron and Ion Sources

ECR Source – Magnetic Mirror

A force acts in the opposite direction to the
Increasing B field



Energy is transferred
from v_{drift} to v_{ecr}

$$v_{drift} = \left\{ \frac{2}{m} (K - \mu B) \right\}^{1/2}$$

$$\mu = \frac{mv_{\perp}^2}{2B} \quad \begin{array}{l} \mu = \text{magnetic moment} \\ K = \text{total kinetic energy} \end{array}$$

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Electron and Ion Sources

Ion Sources - Basics

- ◆ Ion Sources at CERN.
 - Linac2 – Protons - Dupolasmatron
 - Linac3 – Ions (Pb, O, Ar) – ECR
 - ISOLDE – Radioactive ions – Surface, laser, Electron Bombardment.
 - REX-ISOLDE – Charge Breeding – Electron Beam Ion Source.
 - Linac4 – Negative Hydrogen – RF

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Electron and Ion Sources

Ion Source – Gas Discharge

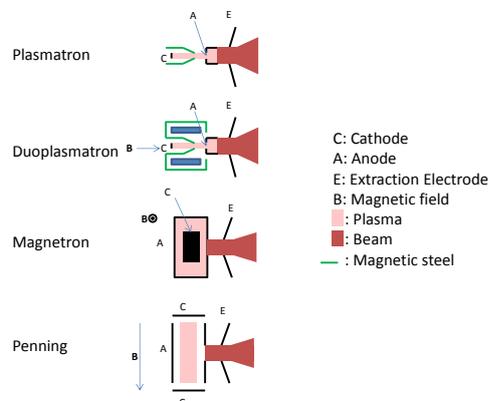
- ◆ Many sources work on the principle of a cathode – anode gas discharge
- ◆ The gas can be a compound form (e.g. Carbon from CO) or from a vapour (e.g. lead vapour from an oven).
- ◆ Electrons from a hot cathode are accelerated into the gas by a cathode to anode voltage, and ionize the gas atoms/molecules with electron impact ionization.
- ◆ At low gas pressures, most electrons do not cause ionization and the ion density remains low.
- ◆ At higher pressures, the electrons cause ionization, which also leads to new electrons to be accelerated and cause ionization.

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Electron and Ion Sources

- ◆ By applying an magnetic field, electrons can have longer path lengths inside the source, and the chance of ionization is increased.

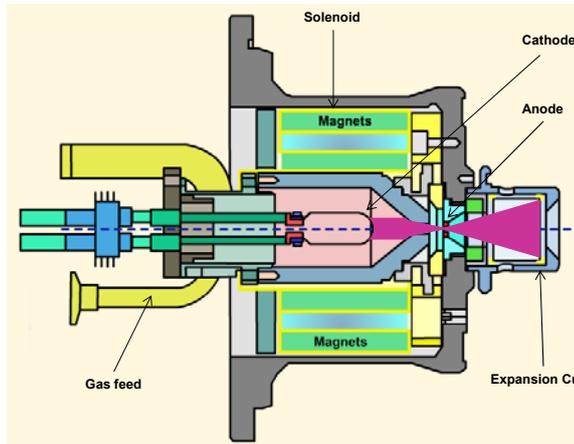


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Electron and Ion Sources

Ion Source – Duoplasmatron – Linac2



Proton Current	200 mA
Proton Energy	90 keV
Emittance	~0.4 mm.mrad
Pulse for LHC	20us @ 1 Hz
# protons / pulse	2.5×10^{13}
# LHC bunches	~24 *

* Creation of LHC bunches is a complicated process, this is an example for 50ns LHC bunches

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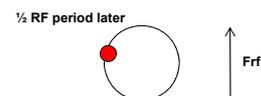
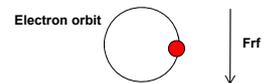
Electron and Ion Sources

Ion Source – ECR – Linac3

- ◆ **Electron Cyclotron Resonance Ion Source (ECR)**
- ◆ For a given magnetic field, non-relativistic electrons have a fixed revolution frequency.
- ◆ The plasma electrons will absorb energy at this frequency (just as particles in a cyclotron).
- ◆ If confined in a magnetic bottle, the electrons can be heated to the keV and even MeV range.
- ◆ Ions also trapped by the charge of the electrons, but for milli-seconds allowing multiple ionisation.
- ◆ The solenoid magnetic field still allows losses on axis – these ions make the beam.

$$\omega_{ecr} = \frac{eB}{m}$$

$$f_{ce} [\text{GHz}] = 28 \times B [\text{T}]$$

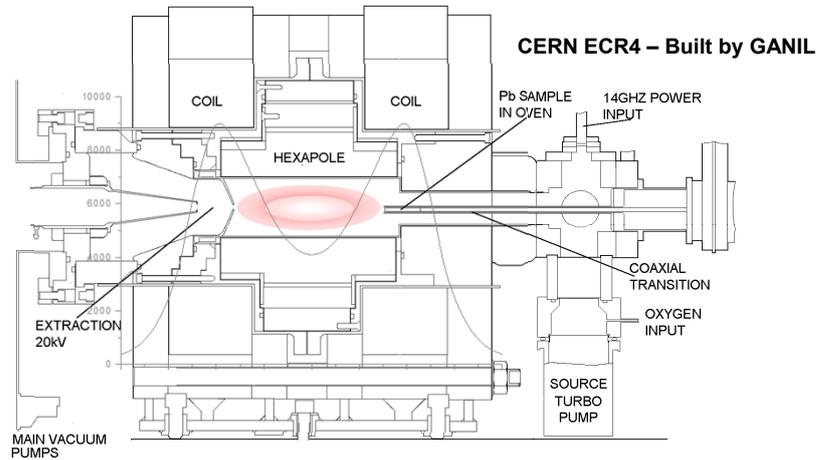


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Electron and Ion Sources

Ion Source – ECR



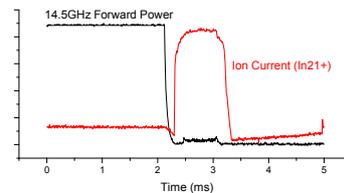
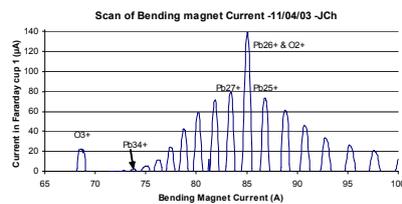
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Electron and Ion Sources

Ion Source – ECR – High charge states

- ◆ No filament is needed, greatly increasing the source lifetime.
- ◆ Singly, multiply and highly charged ions can be produced by these sources (although the source construction will influence this).
 $A \rightarrow A^+ \rightarrow A^{2+} \rightarrow A^{3+}$
Stepwise ionisation.
- ◆ Gaseous ions are easily made. Metallic ions come from an OVEN or from a compound gas (e.g UF₆ for uranium).
- ◆ In the afterglow mode, the ion intensity increases AFTER switching off the micro-waves.



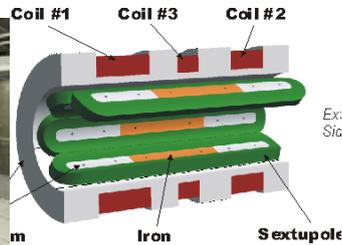
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Electron and Ion Sources

Ion Source – ECR – High charge states + industry solutions

- ◆ Plasma density increases with frequency and associated magnetic field.
- ◆ Example: VENUS source and Berkeley, Ca, uses superconducting solenoid and sextapole magnets.
- ◆ Industry can now provide turnkey solutions for ECR ions sources, usually using permanent magnets.



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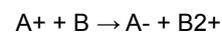
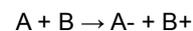
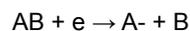
Electron and Ion Sources

Ion Sources – Negative Ions

- ◆ Negative ion sources allow:
Charge exchange injection into synchrotrons.
Charge exchange extraction from cyclotrons.
Tandem accelerators.

	Electron Affinity (eV)
H	0.7542
He	<0
Li	0.6182
Be	<0
B	0.277
C	1.2629
N	<0
O	1.462
F	3.399

- ◆ The bonding energy for an electron onto an atom is the Electron Affinity.
- ◆ $E_a < 0$ for Noble Gases
- ◆ Large E_a for Halogens
- ◆ Two categories of negative ion sources
 - Surface – an atom on a surface can be desorbed with an extra electron (whose wave-function overlapped the atom).
 - Volume – Through collisions, e-capture and molecular dissociation, negative ions can be formed.

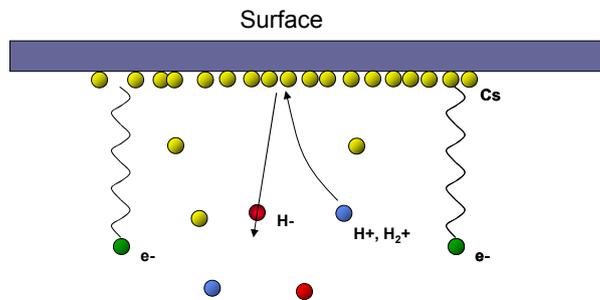


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Electron and Ion Sources

H- Surface Ion Production



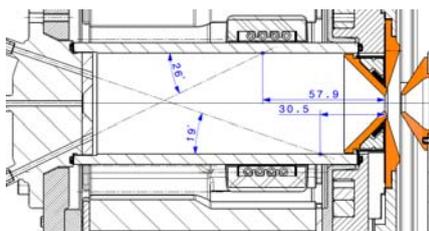
- ◆ Protons from the plasma are accelerated to the cathode, which has a coating of caesium.
- ◆ The protons desorbed from the low work function surface, with an additional electron.
- ◆ The plasma must not be too hot, to avoid ionising the H-.
- ◆ Penning, Magnetron, etc, sources produce H this way.

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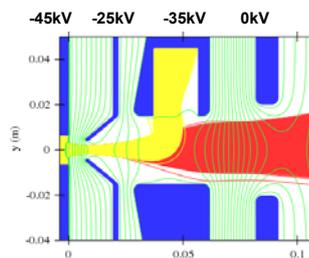


Electron and Ion Sources

Ion Sources – Negative Ions – Linac4



- ◆ Plasma is created using 2MHz RF in a solenoid coil.
- ◆ A surface near the extraction is coated with caesium, evaporated from an oven at the back of the source.
- ◆ The plasma protons strike the cesium surface and H- are emitted.



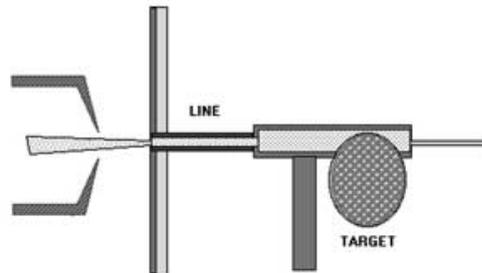
- ◆ Electrons (yellow) are extracted along with negative ions (red).
- ◆ Electrons can be separated with a dipole B field in extraction.
- ◆ In the Linac4 RF source (without cesium) >1A of electrons are extracted.

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Electron and Ion Sources

Ion Source – Radioactive Ions – ISOLDE



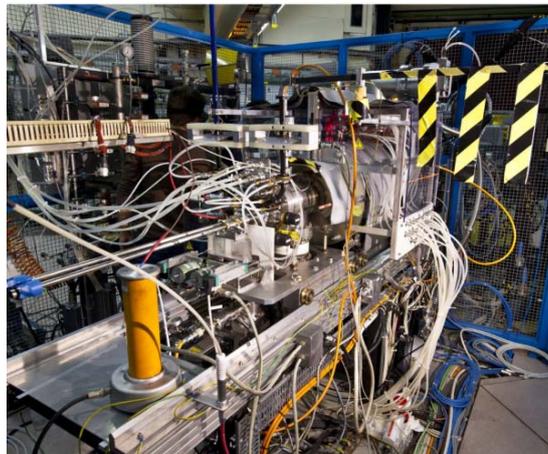
- ◆ A gas/vapour of new isotopes is produced from 1.4GeV protons onto a target.
- ◆ The ion source is used to ionize the gas.
- ◆ The ions will be mass selected in an ion spectrometer.
- ◆ The sources can help to reduce the contamination (i.e. stable/other isotopes of the same mass) through some selective process (e.g. using lasers to selectively ionize).

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Electron and Ion Sources

- ◆ For sources, all we have see so far is the ion generation.
- ◆ You still have to add the high voltage systems, pumping, cooling, power convertors, controls...



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Electron and Ion Sources

Summary

- ◆ **Electron Source Summary**
 - Thermionic Source. Some thermal electrons are above the Work-Function.
 - Use low work-function or high melting point materials to obtain the most electrons
 - Photo-cathodes – Use photons above the work-function or $E_g + E_a$.
 - Metals – Stable but have a low quantum efficiency
 - Semiconductors – high Q, but can be unstable and degrade in use.

- ◆ **Ion Source Summary**
 - Plasmas are a common production method for ions.
 - There are many ways to produce, heat and confine a plasma, leading to many source types.
 - CERN already uses quite an array of these types.

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Electron and Ion Sources

Further Reading

- ◆ **Handbook of Ion Source, B. Wolf, Boca Raton, FL: CRC Press, 1995**
- ◆ **Ion Sources, Zhang Hua Shun, Berlin: Springer, 1999.**
- ◆ **The Physics and Technology of Ion Source, I. G. Brown, New York, NY: Wiley, 1989**
- ◆ **Large Ion Beams: Fundamentals of Generation and Propagation, T. A. Forrester, New York, NY: Wiley, 1988**
- ◆ **CAS – 5th General School (CERN 94-01) and Cyclotrons, Linacs... (CERN-96-02)**

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Electron and Ion Sources

◆ Some Final Words

- Electron and ion sources still represent a challenging topic for particle accelerators.
- Demands continue to be for high intensities, lower emittances, shorter pulses (for electrons), high charge states (for high charge state ion sources), as well as improvements to the reliability and stability of these sources.
- Taking into account the varied nature of solutions for these devices (thermionic, photo cathode with different types, *Wolf* lists 14 species of ions sources) there is plenty of scope for scientists to make a impact in the field.
- This is an exciting field, that urgently needs new recruits!
- ...and don't forget, accelerators will ALWAYS need particle sources.

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Electron and Ion Sources

Thank you for your attention.

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Electron and Ion Sources

A: Richardson-Dushman constant
E: Particle Energy
E: Electric field
J: Current density
n: particle density
T: Temperature
U,V: Voltage
 v : particle velocity
 β : Relativistic beta
 γ : Relativistic gamma